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(71)Applicant : DAINIPPON SCREEN MFG CO LTD

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(72)Inventor : MURAOKA YUSUKE

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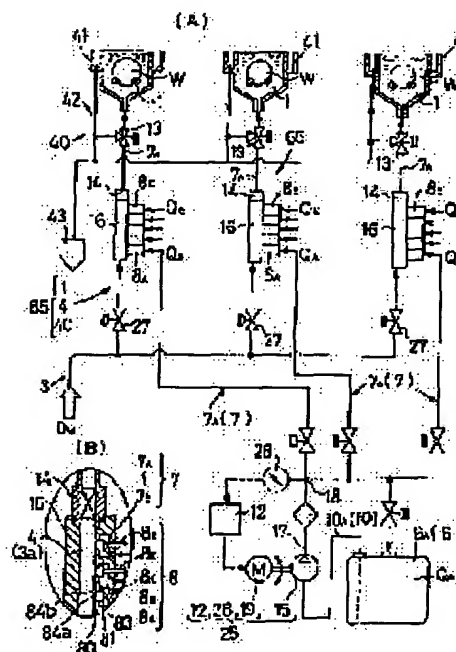
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(54) SUBSTRATE PROCESSOR

(57)Abstract:

PURPOSE: To increase the throughput of a substrate processor performing such operation as the surface treatment of a semiconductor substrate, etc., thereby saving the installation space of the whole device.

CONSTITUTION: Multiple overflow type semiconductor treatment vessels 1 are juxtaposed so as to branch the treatment solution leading-in pipes 10 led from a treatment solution reservoir 6 for respectively connecting the branching ends to the feed pipes 7 of respective substrate cleaning vessels through the intermediary of treatment solution leading-in valves 8. Through these procedures, multiple substrates can be parallel-processed in multiple substrate treatment vessels 1 to increase the throughput thereof. At this time, only one set of reservoir 6 can suffice for multiple substrate treatment vessels 1 thereby enabling the space of the whole processor device to be saved.



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